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FACSIMILE TRANSMISSION

DATE: February 6, 2006

TO: Examiner Stephen Rosasco
571-273-1389

FROM: Scott L. Appelbaum, Esq.
F. Chau & Associates, LLC

NO. OF PAGES TO FOLLOW: 39

Re: U.S. Appln. Serial No. 10/688,591
PHASE EDGE PHASE SHIFT MASK ENFORCING
A WIDTH OF A FIELD OF GATE IMAGE AND
FABRICATION METHOD THEREOF
Our Docket: 8028-28

MESSAGE:

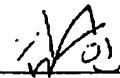
As discussed earlier this afternoon, attached please find an English translation of the certified copy of the priority application along with the verified statement in support of certain arguments made in the Amendment filed with the U.S. Patent and Trademark Office on January 26, 2006.

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VERIFICATION OF TRANSLATION

I, Seung-In KIM, of Suite 1810, Hwanghwa Bldg., 832-7, Yeoksam-dong, Gangnam-gu, Seoul, Republic of Korea hereby declare that I am knowledgeable in the English and Korean languages, and that to the best of my knowledge the attached document is true and complete English translation of the patent application of Korean Patent Application No. 2002-64641.

Dated February 3, 2006



Signature